

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

DELIBERATE SEMICONDUCTOR FILM VARIATION TO
COMPENSATE FOR RADIAL PROCESSING DIFFERENCES,
DETERMINE OPTIMAL DEVICE CHARACTERISTICS, OR
PRODUCE SMALL PRODUCTIONS

Application Number :

Confirmation Number:

First Named Applicant: Toshiharu Furukawa

Attorney Docket Number: BUR919990179US3

Art Unit: 2825

Examiner: Renzo Rocchegiani

Search string: (5759634 or 5650197 or 5571322 or 5534314 or 5356673 or 5356672 or 4788082
or 6200834 or 6043530 or 6432768 or 6444531 or 6242300 or 6333222 or 6331462
or 6369421 or 5378909).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
H	1	5759634	1998-06-02	Zang			
	2	5650197	1997-07-22	Halpern			
	3	5571322	1996-11-05	Halpern			
	4	5534314	1996-07-09	Wadley, et al.			
	5	5356673	1994-10-18	Schmitt, et al.			
	6	5356672	1994-10-18	Schmitt, III et al.			
	7	4788082	1988-11-29	Schmitt			
	8	6200834	2001-03-13	Bronner et al.			
	9	6043530	2000-03-28	Chang			
	10	6432768	2002-08-13	Chien et al.			
	11	6444531	2002-09-03	Rupp et al.			
	12	6242300	2001-06-05	Wang			
	13	6333222	2001-12-25	Kitazawa et al.			
	14	6331462	2001-12-18	Kasaoka et al.			
	15	6369421	2002-04-09	Xiang et al.			
HP	16	5378909	1995-01-03	Chang et al.			

Remarks

Note: Remarks are not for responding to an office action.

28 Article: Zhang, et al., "Jet Vapor Deposition: A New, Low Cost Metallization Process", 1997 International Symposium on Microelectronics.

Signature

Examiner Name	Date
R. Picard	9/28/04